

	Hits	Search Text	DBs
75	49	((ion near9 beam) or ion) same (ash\$4 or harden\$4 or (sputter\$4 near16 beam) or (sputter near9 etch\$4) or imping\$4 or irradiat\$4 or bombard\$5) same (resist or photoresist or BARC or (organic near9 BARC) or (organic near9 resist) or (photosensitive near9 mask)) same (overhang or terrace or undercut\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
76	38	((resist or photoresist) same ozone same treat\$4) and lift\$5off and ((plasma or irradiat\$4 or expos\$4 or illuminat\$4) same (oxygen or ozone or "O.sub.3"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
77	1	((resist or photoresist or photolithograph\$5 or lithograph\$5) same (mask or pattern) same ozone same treat\$4) and lift\$5off and ((plasma or irradiat\$4 or expos\$\$ or illuminat\$4) same (terrace or overhang))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
78	5	((resist or photoresist or photolithograph\$5 or lithograph\$5) same (mask or pattern) same (oxidation or ozone or ashing) same treat\$4) and lift\$5off and ((plasma or irradiat\$4 or expos\$\$ or illuminat\$4) same (terrace or overhang))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB